

Amendments to the Specification

Please replace the title with the following amended title:

METHODS FOR MASKLESS LITHOGRAPHY ~~DEVICE FOR SEMICONDUCTOR CIRCUIT PATTERN GENERATION~~

Please add the following new paragraph, as provided between ending "--" and closing "--", on page 1 as the first sentence of the specification directly following the title:

--Cross Reference to Related Applications

This application is a continuation of copending, commonly assigned United States Patent Application No. 08/483,731, filed June 7, 1995, which is a continuation of United States Patent Application No. 08/315,905, filed September 30, 1994, now U.S. Patent No. 5,869,354, which is a division of United State Patent Application No. 07/865,412, filed April 8, 1992, now U.S. Patent No. 5,354,695, all of which are incorporated by reference herein in their entireties.--

Please replace the paragraph that begins at page 9, line 2 and ends at page 9, line 3 with the following amended version of that paragraph, as provided between ending "--" and closing "--". As this is not a new paragraph, amendments are shown. Particularly, additions are underlined and deletions are struck out.

--Figures 29l to 29n and 29p show use of fixed freestanding membrane lithography masks.--

Please add the following new paragraph, as provided between ending "--" and closing "--", after page 9, line 9 and before page 9, line 10 of the specification.

--Figures 32c and 32d show die cut from a circuit membrane and bonded onto a rigid substrate.--